Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	3	(("5804473") or ("5994172") or ("6413805")).PN.	USPAT; USOCR	OR	OFF	2005/03/25 15:10
L2	12	spin adj method and catalyst	USPAT	OR	OFF	2005/03/25 15:33
L3	6	spin adj method and organic adj solution	USPAT	OR	OFF	2005/03/25 15:22
L4	2	spin adj method and metallic adj element	USPAT	OR	OFF	2005/03/25 16:17
L5	2	spin adj method and metallic adj oxide	USPAT	OR	OFF	2005/03/25 15:22
L6	13	spin adj method and silicon adj oxide	USPAT	OR	OFF	2005/03/25 15:22
L7	15	spin adj method and titanium adj oxide	USPAT	OR	OFF	2005/03/25 15:22
L8	4	spin adj method and zirconium adj oxide	USPAT	OR	OFF	2005/03/25 16:51
L9	13	spin adj method and fluoride	USPAT	OR	OFF	2005/03/25 15:23
L10	0	spin adj method and rotational adj acceleration	USPAT <sub>.</sub>	OR	OFF	2005/03/25 15:36
L11	613	(438/96-97).CCLS.	USPAT; USOCR	OR	OFF	2005/03/25 15:24
L12	682	(438/166).CCLS.	USPAT; USOCR	OR	OFF	2005/03/25 15:24
L13	219	(438/365).CCLS.	USPAT; USOCR	OR	OFF	2005/03/25 15:25
L14	1644	(438/482-489).CCLS.	USPAT; USOCR	OR	OFF	2005/03/25 15:25
L15	2172	(438/758-764).CCLS.	USPAT; USOCR	OR	OFF	2005/03/25 15:25
L16	1200	(438/780-782).CCLS.	USPAT; USOCR	OR	OFF	2005/03/25 15:25
L17	201	(438/769).CCLS.	USPAT; USOCR	OR	OFF	2005/03/25 15:25
L18	490	(438/789-790).CCLS.	USPAT; USOCR	OR	OFF	2005/03/25 15:26
L19	67	(438/793-794).CCLS.	USPAT; USOCR	OR	OFF	2005/03/25 15:40
L20	91	(438/969).CCLS.	USPAT; USOCR	OR	OFF	2005/03/25 15:32
L21	987	(427/424).CCLS.	USPAT; USOCR	OR	OFF	2005/03/25 15:32
L22	496	(427/425).CCLS.	USPAT; USOCR	OR	OFF	2005/03/25 15:32

L23	138	(427/498).CCLS.	USPAT; USOCR	OR	OFF	2005/03/25 15:32
L24	306	(427/512).CCLS.	USPAT; USOCR	OR ·	OFF	2005/03/25 16:21
L25	251766	catalyst	USPAT	OR	OFF	2005/03/25 15:52
L26	24	125 and 111	USPAT	OR	OFF	2005/03/25 15:52
L27	165	I25 and I12	USPAT	OR	OFF	2005/03/25 15:33
L28	0	I25 and I13	USPAT	OR	OFF	2005/03/25 15:33
L29	166	I25 and I14	USPAT	OR	OFF	2005/03/25 15:33
L30	97	I25 and I15	USPAT	OR	OFF	2005/03/25 15:33
L31	153	I25 and I16	USPAT	OR	OFF	2005/03/25 15:33
L32	11	125 and 117	USPAT	OR	OFF	2005/03/25 15:33
L33	53	125 and 118	USPAT	OR	OFF	2005/03/25 15:34
L34	4	I25 and I19	USPAT	OR	OFF	2005/03/25 15:34
L35	0	125 and 120	USPAT	OR	OFF	2005/03/25 15:34
L36	39	125 and 121	USPAT	OR	OFF	2005/03/25 15:34
L37	, 32	I25 and I22	USPAT	OR	OFF	2005/03/25 15:34
L38	35	125 and 123	USPAT	OR	OFF	2005/03/25 15:34
L39	82	125 and 124	USPAT	OR	OFF	2005/03/25 15:34
L40	2	spin adj method and angular adj velocity	USPAT	OR	OFF	2005/03/25 15:39
L41	0	spin adj method and angular adj acceleration	USPAT	OR	OFF	2005/03/25 16:50
L42	339	spin and angular adj acceleration	USPAT	OR	OFF	2005/03/25 16:39
L43	0	126 and 127 and 128 and 129 and 130 and 131 and 132 and 133 and 134 and 135 and 136 and 137 and 138 and 139	USPAT	OR	OFF	2005/03/25 15:51
L44	9530	catalyst and spin	USPAT	OR T	OFF	2005/03/25 16:22
L45	5	l44 and l11	USPAT	OR	OFF	2005/03/25 15:54
L46	108	144 and 112	USPAT	OR	OFF	2005/03/25 15:58
L47	0	144 and 113	USPAT	OŘ	OFF	2005/03/25 15:53
L48	92	l44 and l14	USPAT	OR	OFF	2005/03/25 16:15
L49	55	l44 and l15	USPAT	OR	OFF	2005/03/25 15:53
L50	124	l44 and l16	USPAT	OR	OFF	2005/03/25 15:53
L51	4	144 and 117	USPAT	OR	OFF	2005/03/25 15:53
L52	39	144 and 118	USPAT	OR	OFF	2005/03/25 15:53
L53	1	144 and 119	USPAT	OR	OFF	2005/03/25 15:53
L54	0	144 and 120	USPAT	OR	OFF	2005/03/25 15:53
L55	2	144 and 121	USPAT	OR	OFF	2005/03/25 15:53

L56	9	144 and 122	USPAT	OR	OFF	2005/03/25 15:54
L57	6	144 and 123	USPAT	OR	OFF	2005/03/25 15:54
L58	19	144 and 124	USPAT	OR	OFF	2005/03/25 15:54
L59	9530	I44 and I25	USPAT	OR	OFF	2005/03/25 15:54
L60	2	spin and angular adj acceleration and catalyst	USPAT	OR	OFF	2005/03/25 16:19
L61	1282	(257/49-55).CCLS.	USPAT; USOCR	OR	OFF	2005/03/25 16:21
L62	1100	(257/63-66).CCLS.	USPAT; USOCR	OR	OFF	2005/03/25 16:21
L63	17	144 and 161	USPAT	OR	OFF	2005/03/25 16:22
L64	62	144 and 162	USPAT	OR	OFF	2005/03/25 16:23
L65	95	spin and angular adj acceleration and metal	USPAT	OR	OFF	2005/03/25 16:39
L66	28	spin and angular adj acceleration and metal and (wafer or substrate)	USPAT	OR	OFF	2005/03/25 16:43
L67	41	spin and angular adj acceleration and metal and (wafer or substrate)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/03/25 16:46
L68	0	spin adj method and angular adj acceleration	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2005/03/25 16:50
L69	0	spin adj method and rotational adj acceleration	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2005/03/25 16:50
L70	12	spin adj method and zirconium adj oxide	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR ·	OFF	2005/03/25 16:51

ieee home : Search ieee : Shop : Web account : Contact ieee



## Publications/Services Standards Conferences Careers/Jobs ⊒ = Xal/al/≜

Welcome



	United States Patent and Trademark Office					
Help FAQ Terms IEE	E Peer Review Quick Links Se					
Concept of 1939 Archors  Home  What Can I Access?  Log-out	Your search matched 3 of 1140634 documents.  A maximum of 500 results are displayed, 15 to a page, sorted by Relevance Descending order.  Refine This Search:					
facility of Conseque	You may refine your search by editing the current search expression or enterinew one in the text box.					
O- Jeurnals & Magazines O- Conference Proceedings	wafer and spin coating and acceleration  Check to search within this result set					
O- Standards State	Results Key:  JNL = Journal or Magazine CNF = Conference STD = Standard					
O- By Author O- Basic O- Advanced O- GrossRef  Melocoessatics O- Join IEEE	1 A low temperature wafer-level hermetic MEMS package using UV cu adhesive  Zhi-Hao Liang; Cheng, Y.T.; Hsu, W.; Yuh-Wen Lee; Electronic Components and Technology, 2004. ECTC '04. Proceedings, Volum 2, 1-4 June 2004 Pages:1486 - 1491 Vol.2  [Abstract] [PDF Full-Text (631 KB)] IEEE CNF					
O- Establish IFEE Web Account O- Access the IEEE Member Digital Library O- Access the	The performances of the novel nozzle-scan coating method Ito, S.; Ema, T.; Sho, K.; Okumura, K.; Kitano, T.; Esaki, Y.; Morikawa, M.; Takeshita, K.; Akimoto, M.; Microprocesses and Nanotechnology Conference, 2000 International, 11-13 J 2000 Pages: 298 - 299					
IEEE Enterprise File Cabinet	[Abstract] [PDF Full-Text (132 KB)] IEEE CNF					
🔁 Print Format	Novel coating apparatus using nozzle-scan technique Kitano, T.; Semiconductor Manufacturing, 2000. Proceedings of ISSM 2000. The Ninth International Symposium on , 26-28 Sept. 2000 Pages:395 - 398					
	[Abstract] [PDF Full-Text (403 KB)] IEEE CNF					

Home | Log-out | Journals | Conference Proceedings | Standards | Search by Author | Basic Search | Advanced Search | Join IEEE | Web Account |
New this week | OPAC Linking Information | Your Feedback | Technical Support | Email Alerting | No Robots Please | Release Notes | IEEE Online
Publications | Help | FAQ | Terms | Back to Top

Copyright © 2004 IEEE - All rights reserved